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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/610,498	06/30/2003	Francis G. Celii	TI-34580	5368
23494 7	7590 10/06/2005		EXAM	INER
TEXAS INST	TRUMENTS INCOR	DEO, DUY VU NGUYEN		
P O BOX 655474, M/S 3999 DALLAS, TX 75265			ART UNIT	PAPER NUMBER
ŕ			1765	
			DATE MAIL ED. 10/06/2000	e

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)				
	10/610,498	CELII ET AL.				
Office Action Summary	Examiner	Art Unit				
	DuyVu n. Deo	1765				
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPL' WHICHEVER IS LONGER, FROM THE MAILING D. - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period v. - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a repty be timwill apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D. (35 U.S.C. § 133).				
Status						
2a) ☐ This action is FINAL . 2b) ☐ This 3) ☐ Since this application is in condition for alloward						
Disposition of Claims						
4) Claim(s) 1-17 is/are pending in the application 4a) Of the above claim(s) 14-17 is/are withdray 5) Claim(s) is/are allowed. 6) Claim(s) 1-13 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/o	vn from consideration.					
Application Papers	<i>:</i>					
9)☐ The specification is objected to by the Examine 10)☒ The drawing(s) filed on 30 June 2003 is/are: a Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11)☐ The oath or declaration is objected to by the Examine 11.)⊠ accepted or b)⊡ objected to drawing(s) be held in abeyance. See tion is required if the drawing(s) is obj	e 37 CFR 1.85(a). ected to. See 37 CFR 1.121(d).				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document: 2. Certified copies of the priority document: 3. Copies of the certified copies of the priority document: application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Application ity documents have been receive u (PCT Rule 17.2(a)).	on No ed in this National Stage				
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 9/7/04.	4) Interview Summary (Paper No(s)/Mail Da 5) Notice of Informal Pa					

DETAILED ACTION

Election/Restrictions

1. Applicant's election without traverse of claims 1-13 in the reply filed on 9/9/05 is acknowledged.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. Claims 1, 4, 5, 10 are rejected under 35 U.S.C. 102(e) as being anticipated by Ying et al. (US 2003/0176073).

Ying describes a method for forming a ferroelectric capacitor comprising: providing a dielectric oxide layer on the substrate 210 (paragraph [0016]); forming a barrier 220 over the dielectric layer (paragraph [0017]); providing a first metal Ir layer 230, a ferroelectric PZT layer 240 and a second. Ir metal layer 250 in the order respectively (paragraphs [0018,0019]); forming a TiAlN hardmask over the Ir layer 250 (paragraph [0020]), etching the second Ir layer, the ferroelectric layer, and the first Ir layer using a plasma process at a T about 250-450 degrees C (paragraph [0028]). Wherein the sidewalls of the capacitor have an angle of greater than about 80 degrees (paragraph [0015]).

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Claim Rejections - 35 USC § 103

4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claims 2, 3, 6-9, 11-13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ying as applied to claim 1 above, and further in view of Moise et al. (US 6,211,035).

Ying describes etching the Ir layers using Cl2/O2/N2 and the PZT using Cl2/O2 (table 1). Unlike claimed invention, he doesn't describe the Ir etchant includes CO and the PZT etchant includes BCl3. Moise describes an etching method of Ir and PZT layers wherein he teaches the Cl2 and O2 sources can have BCl3 in addition to the Cl2 and CO in addition to O2 (col. 18, line 65-col. 19, line 13). It would have been obvious for one skilled in the art, in light of Moise, that BCl3 and CO can be added to the etchant of the Ir and PZT layers as a source of Cl2 and O2 to etch the Ir and the PZT layers with a reasonable expectation of success.

Referring to claims 3, 8, and 12, applied prior art of Moise doesn't describe the gases ratios of BCl3 and Cl2 are from 1:4-10:1. However, one skilled in the art would find it obvious to determine the gases ratios from the routine experimentation in order to provide optimum ratios of etching gases including BCl3 and Cl2 to etch the PZT layer with a reasonable expectation of success.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to DuyVu n. Deo whose telephone number is 571-272-1462. The examiner can normally be reached on 6:00-2:30 Mon-Fri.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Primary Examiner Duy-Vu N. Deo

10/3/05